

# EUROPEAN PATENT OFFICE

## Patent Abstracts of Japan

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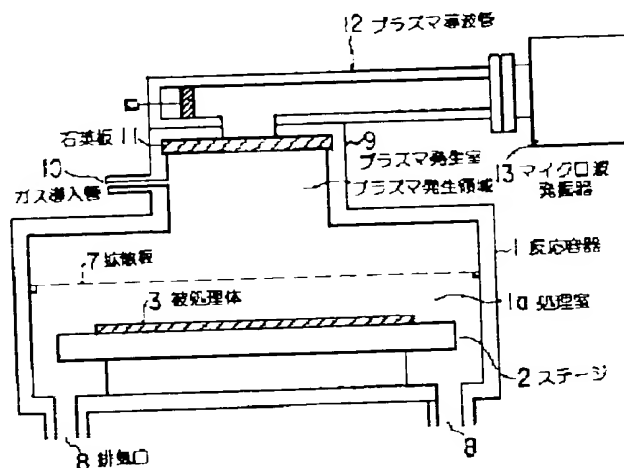
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APPLICANT : TOSHIBA CORP;

INVENTOR : KOJIMA KAYOKO;

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TITLE : ASHING METHOD AND DEVICE



ABSTRACT : PROBLEM TO BE SOLVED: To eliminate an organic thin film by increasing a selection ratio to a ground film.

SOLUTION: A gas for ashing where  $\text{NH}_3$  gas is mixed to  $\text{O}_2$  gas and  $\text{CHF}_2$  gas is introduced into a plasma generation room 9, plasma is generated by introducing microwave, and an organic thin film (resist) 6 formed on a-Si film as a ground film on a body 3 to be treated by an active seed generated by the plasma is eliminated. At this time, ammonium salt is formed on the a-Si film to prevent etching to the a-Si film.

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